

# Nanostructured Ti-WO<sub>3</sub> Thin Films for Gas Sensor Applications

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## Abstract

In this work, undoped and Ti doped WO<sub>3</sub> nanostructured films were prepared on the glass substrate using the electron beam evaporation method and the films microstructural, structural, chemical and gas sensor properties were studied. Undoped WO<sub>3</sub> films show the presence of nanoflakes and the surface appears homogenous and smooth. The nanoflakes are turned into nanorings after doping the Ti into WO<sub>3</sub>. The target gases were tested at room temperature (30°C) with the same concentration. The Ti-WO<sub>3</sub> sensor possesses excellent selectivity towards hydrogen gas compared to other gases.

**Keywords:** Thin films, Tungsten oxide, Electron beam evaporation, Nanostructure, Gas sensors.

## Introduction

In recent years, the demand for gas sensors has greatly increased in different fields such as military, environmental protection, industries and civil fields<sup>19</sup>. Gas sensors detect diverse gases including asphyxiating gases, volatile organic compounds and irritating gases. The sensing materials play a key role in gas sensors, which could interact with target gases. The sensing materials properties such as surface microstructure, electronic properties, flexibility and compatibility with substrates improve the sensing performance of gas sensors. In the past few decades, metal oxide semiconductors (MOSs) such as SnO<sub>2</sub>, ZnO, TiO<sub>2</sub>, Fe<sub>2</sub>O<sub>3</sub>, InGaZnO, NiO, CuAlO<sub>2</sub> and WO<sub>3</sub> are generally applied as gas sensitive materials owing to their low cost, high transparency, easy fabrication method, reproducibility and high sensitivities<sup>1,2,13,11</sup>.

Among these MOSs, tungsten oxide (WO<sub>3</sub>) is one of the most promising materials due to its outstanding properties and it possesses a variety of applications like sensors, antibacterial coatings, batteries, electrochromic and photochromic and photocatalysis<sup>4,5,9,16,17,21</sup>. To enhance gas sensing properties, WO<sub>3</sub> is often modified with an adequate quantity of noble metals or transition metals<sup>10,15</sup>. WO<sub>3</sub> based thin films are prepared using several methods such as electron beam evaporation<sup>8</sup>, sputtering<sup>18</sup>, spray pyrolysis<sup>7</sup> and electrodeposition-assisted sol-gel method<sup>20</sup>. In this work, WO<sub>3</sub> and Ti-doped WO<sub>3</sub> nanostructured films were prepared by electron beam evaporation and the gas sensor properties were studied.

## Material and Methods

The nanostructured tungsten oxide (WO<sub>3</sub>) and Ti-doped tungsten oxide (Ti-WO<sub>3</sub>) thin films were prepared by electron beam evaporation technique onto the glass substrates using high purity (99.99%) WO<sub>3</sub> and Ti-WO<sub>3</sub> pellets. Table 1 lists the parameters that were maintained during the film deposition process.

**Characterization of nanostructured WO<sub>3</sub> and Ti-WO<sub>3</sub> films:** The microstructure was investigated through scanning electron microscopy (SEM), while the structural characteristics of the films were assessed using an X-ray diffractometer (XRD). The chemical composition was analyzed using X-ray photoelectron spectroscopy (XPS).

## Results and Discussion

**Microstructure:** The SEM images of undoped and Ti doped nanostructured WO<sub>3</sub> films are illustrated in fig. 1(a-d). Undoped WO<sub>3</sub> films show the presence of nanoflakes and the surface appears homogenous and smooth as in fig. 1(a) revealing the amorphous character of the films.

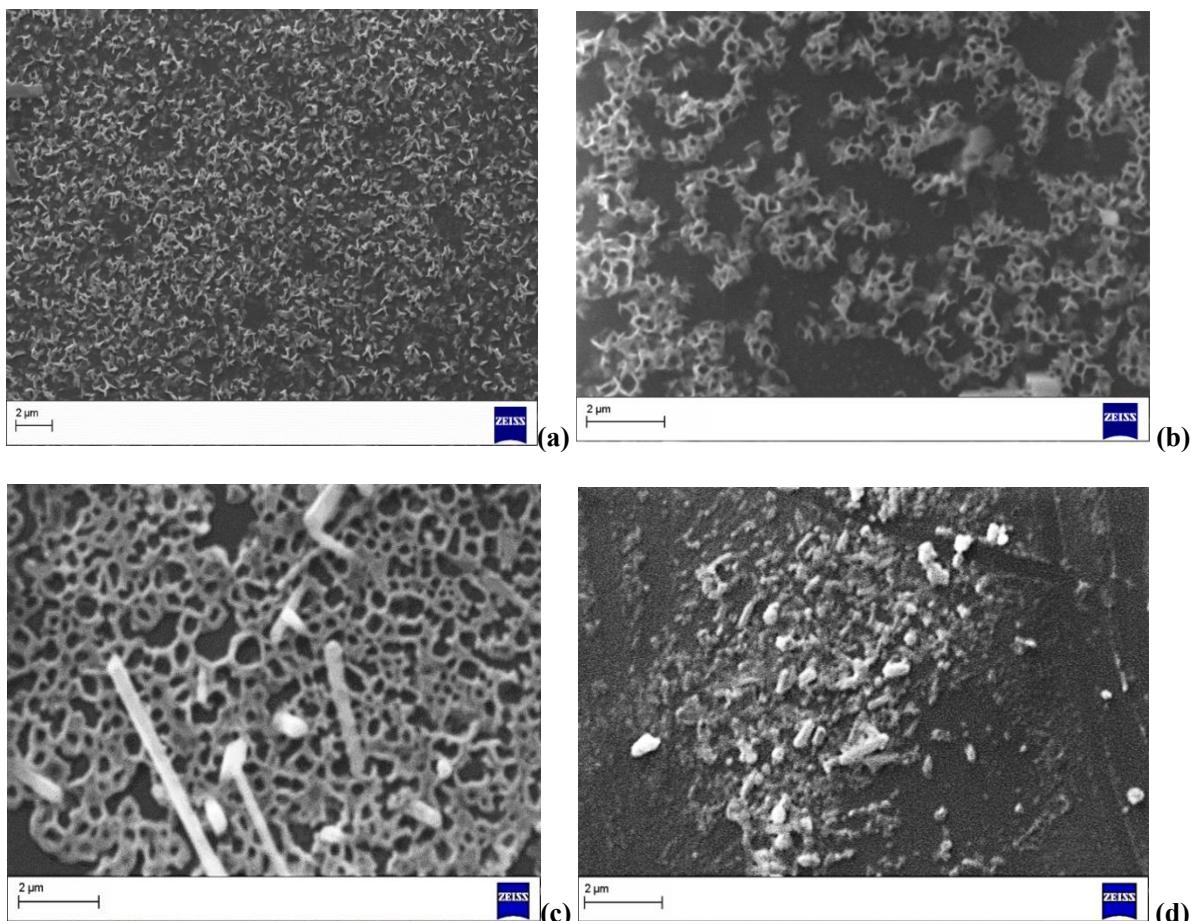
Table 1

The parameters maintained during the deposition of the undoped and Ti doped WO<sub>3</sub> films

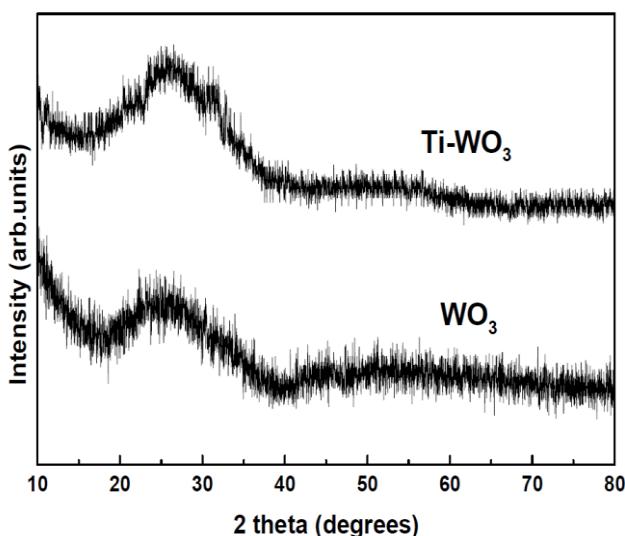
S.N.	Parameters	WO <sub>3</sub> Films	Ti-WO <sub>3</sub> Films		
			5 wt%	10 wt%	15 wt%
1	Accelerating Voltage (kV)	48	48	48	48
2	Accelerating Current (mA)	1.3	1.3	1.3	1.3
3	Base Pressure (mbar)	3.8 x 10 <sup>-6</sup>	3.8 x 10 <sup>-6</sup>	3.8 x 10 <sup>-6</sup>	3.8 x 10 <sup>-6</sup>
4	Deposition Pressure (mbar)	1 x 10 <sup>-3</sup>	1 x 10 <sup>-3</sup>	1 x 10 <sup>-3</sup>	1 x 10 <sup>-3</sup>
5	Deposition Time (min)	10	12	12	12
6	Deposition Temperature	Room Temperature	Room Temperature	Room Temperature	Room Temperature

The nanoflakes are turned into nanorings and formed as clusters by adding the 5wt% of Ti to  $\text{WO}_3$  as in fig. 1(b). On further increasing the dopant of Ti in  $\text{WO}_3$  to 10wt%, the nanorings are clearly formed with some nanorods and clusters disappear as in fig. 1(c). The nanorings disappeared completely with the increase of the Ti content in  $\text{WO}_3$  to about 15wt% and the microstructure appeared with uneven/random nanostructure with tiny nanorods as in fig.

1(d). These results indicate that Ti doping can lead to considerable microstructural changes in  $\text{WO}_3$  films. In the literature, Cai et al<sup>4</sup> observed similar microstructural changes in template-free hydrothermal method Ti doped  $\text{WO}_3$  films. The undoped films exhibited porous and nanoscale interconnecting network structures. The macroporous surface and star-like structures were formed after adding the Ti to  $\text{WO}_3$ .



**Fig. 1: SEM images of undoped and Ti doped  $\text{WO}_3$  films: (a) undoped, (b) 5wt% Ti doped  $\text{WO}_3$ , (c) 10wt% Ti doped  $\text{WO}_3$  and (d) 15wt% Ti doped  $\text{WO}_3$ .**



**Fig. 2: XRD patterns of undoped and Ti doped  $\text{WO}_3$  films: (a) undoped, (b) 10wt% Ti doped  $\text{WO}_3$ .**

**Structural analysis:** The XRD patterns of the undoped and Ti doped  $\text{WO}_3$  films are shown in fig. 2. The X-ray diffraction pattern of  $\text{WO}_3$  films show no distinct diffraction peaks indicating amorphous in nature due to the low energy of tungsten oxide ions reaching the surface of the substrate and these low energy ions will prevent the crystallization of the  $\text{WO}_3$  films. Consequently, the amorphous phase was obtained<sup>14</sup>. The addition of different wt% of Ti into  $\text{WO}_3$  did not improve the crystal structure of  $\text{WO}_3$  films and no peaks related to Ti, W,  $\text{WO}_3$  or titanium oxide phases. Ti doping produces defect states, resulting in structural disorder in the  $\text{WO}_3$ .

The amount of defect states and structural disorder produced due to the doping of Ti may destabilize the  $\text{WO}_3$  crystal structure leading to an amorphous structure. The broad hump appeared between diffraction angle  $20^\circ$  and  $30^\circ$  originating from the glass substrate<sup>3</sup>.

**XPS analysis:** XPS is used to analyze the binding energy of the films and to identify trace elements of Ti doped  $\text{WO}_3$  nanostructure films. Fig. 3(a-c) illustrates a typical XPS spectrum for the surface of a nanostructured 10wt% Ti doped  $\text{WO}_3$  films and the films contained only the constituent elements such as W, O and Ti. Fig. 3 (a) shows the 4f spectrum of the  $\text{WO}_3$ . The spectrum doublets indicate the chemical states of tungsten (W) along with their associated binding energy peaks at 35.2 eV and 37.4 eV, corresponding to W 4f<sub>7/2</sub> and W 4f<sub>5/2</sub> respectively.

In fig. 3(b), the O 1s spectrum reveals a peak at 529.8 eV. In the context of transition metal oxides, two types of O 1s peaks can be identified: one associated with the  $\text{O}^{2-}$  peak in the range of 529.5 to 530.5 eV, which is characteristic of crystalline sites and the other peaks linked to  $\text{O}^-$  in the 531 to 532 eV range, typically found in sub-surface regions<sup>6</sup>.

The Ti 2p XPS spectrum for the 10 wt% Ti-doped  $\text{WO}_3$  film is illustrated in fig. 3(c) where it can be fitted with two doublets. Due to the relatively low concentration of Ti in the  $\text{WO}_3$  matrix, the peaks are not distinctly resolved. The

primary peak of the first doublet is located at 455.3 eV while the satellite peak appears at 463.6 eV, corresponding to Ti 2p<sub>3/2</sub> and Ti 2p<sub>1/2</sub> respectively.

**Gas sensor properties:** The gas sensing response was measured in a test chamber using a two-probe method to measure the film resistance. The measurement was conducted in a closed chamber that included a substrate heater and sample holder. Hydrogen and various alcohol vapors (ammonia, methanol, formaldehyde) were used as target gases to characterize the sensing capabilities of the undoped and Ti doped  $\text{WO}_3$  sensors and the flow of gases monitored by the mass flow controller. The sample's operating temperature was controlled by a proportional-integral-derivative (PID) controller, connected to the heating component located at the rear of the sensor holder.

Selectivity is one of the important parameters of gas sensors. In this work, the selectivity of the gas sensor was analyzed by comparing the responses of hydrogen, ammonia, methanol and formaldehyde (Fig.4). All the target gases were examined at room temperature (30°C) with the same concentration. The Ti- $\text{WO}_3$  sensor possesses excellent selectivity for hydrogen gas compared to other target gases.

The important parameter for evaluating a sensor is to determine its optimum operating temperature. In this work, the sensor was examined within the operating temperature range of 30 °C-300 °C. Fig. 5 shows the effect of operating temperature on the hydrogen sensing behavior of 10wt% Ti doped  $\text{WO}_3$  thin film. The resistance of gas sensing material decreased significantly with the increase in temperature. The present obtained resistance drop values are 4.35k $\Omega$ , 4.96k $\Omega$  and 3.70k $\Omega$ , for the operating temperatures of 30°C, 150°C and 300°C respectively.

By increasing the operating temperature, the target gas molecules became more and more active, consequently the resistance drop values are increased. At a higher operating temperature of 300°C, the resistance drop value is minimal due to the deterioration of the gas diffusion<sup>12</sup>.

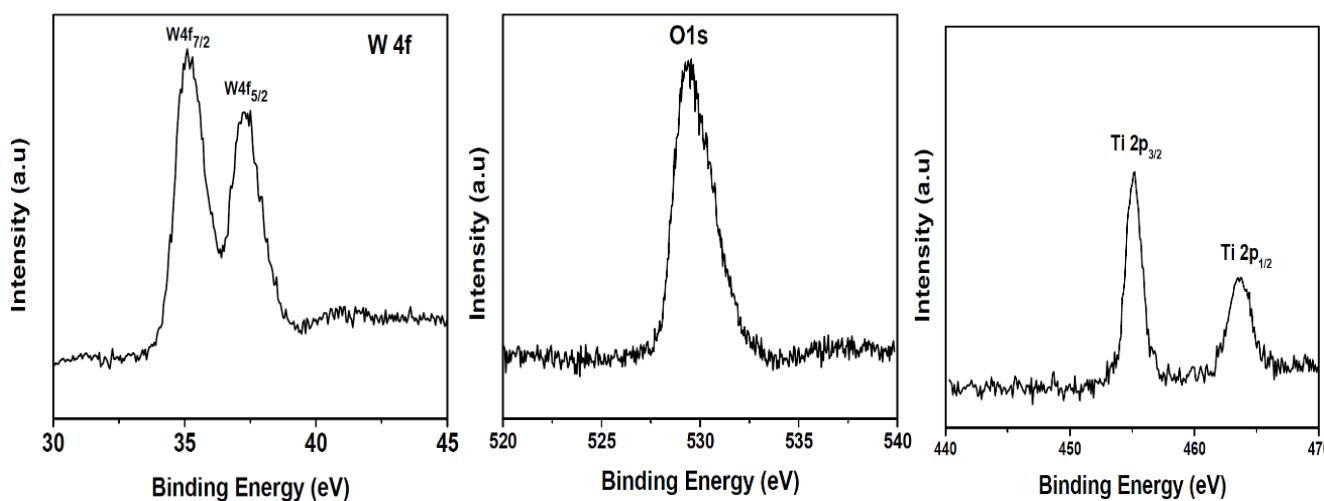


Fig. 3: XPS spectra of nanostructured 10wt% Ti doped  $\text{WO}_3$  films.

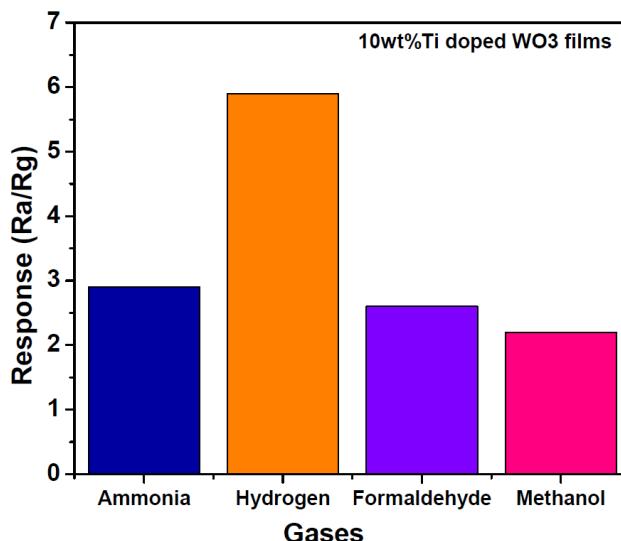


Fig. 4: Response of nanostructure 10wt% Ti doped  $\text{WO}_3$  films at different gases.

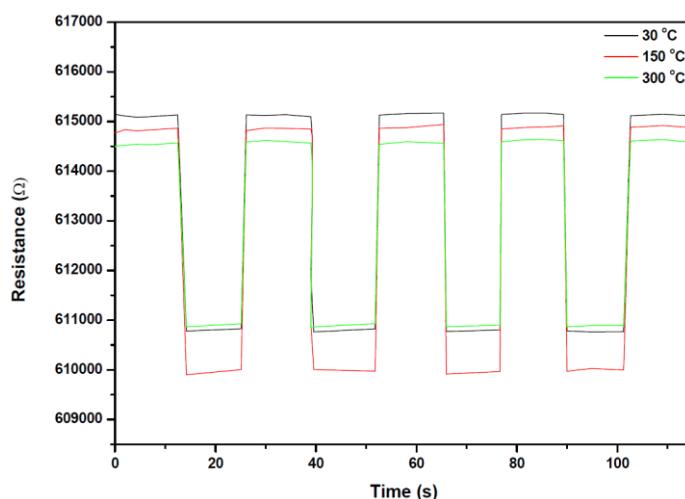


Fig. 5: Effect of operating temperature on the hydrogen sensing behavior of 10wt% Ti doped  $\text{WO}_3$  thin film.

## Conclusion

Undoped and Ti doped  $\text{WO}_3$  nanostructured films were prepared on the glass substrate using the electron beam evaporation method and the microstructural, structural, chemical and gas sensor properties were studied. Undoped  $\text{WO}_3$  films show the presence of nanoflakes and the surface appears homogenous and smooth. The nanoflakes are turned into nanorings after adding the 10wt% of Ti to  $\text{WO}_3$ . The X-ray diffraction pattern of undoped and Ti doped  $\text{WO}_3$  films shows no distinct diffraction peaks, indicating amorphous in nature. XPS is employed to investigate the binding energy of the films and to identify trace elements of Ti doped  $\text{WO}_3$  nanostructure films.

The films contained only the constituent elements such as W, O and Ti. The Ti- $\text{WO}_3$  sensor possesses excellent selectivity towards hydrogen gas compared to other gases. The resistance of gas sensing material decreased significantly with increasing operating temperature. The electron beam evaporated nanoring structured Ti doped  $\text{WO}_3$  film is a simple and cost-effective way and can be used for gas sensor applications.

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